



DRM PTO-1449 US Dept. of Commerce Patent and Trademark Office	ATTORNEY DOCKET NO.	SERIAL NO.
	ATMI-515	10/015,326
	APPLICANT Chongying Xu, et al.	
	FILING DATE December 13, 2001	GROUP TBA

INFORMATION DISCLOSURE STATEMENT
(use several sheets if necessary)

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>LM</i>	AA	5,204,134	4/20/1993	Kirlin, et al.			
	AB	5,536,323	7/16/1996	Kirlin, et al.			
	AC	5,711,816	1/27/1998	Kirlin, et al.			
	AD	6,171,945	1/9/2002	Mandal, et al.			
	AE	4,745,169	5/17/1988	Sugiyama, et al.			
	AF	4,755,370	7/5/1988	Kray, et al.			
	AG	6,114,500	9/5/2000	Mori, et al.			
	AH	5,043,789	8/27/1991	Linde, et al.			
	AI	4,871,616	10/3/1989	Kimura, et al.			
	AJ	5,484,867	1/16/1996	Lichtenhan, et al.			
	AK	4,670,299	6/2/1987	Fukuyama, et al.			
	AL	5,047,492	9/10/1991	Weidner, et al.			
	AM	5,210,250	5/11/1993	Watanuki, et al.			
	AN	4,374,110	2/15/1983	Darnell, et al.			
	AO	4,156,689	5/29/1979	Ashby, et al.			
<i>LM</i>	AP	5,804,040	9/8/1998	Asai, et al.			

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES	NO
							X (abstract only)	
<i>LM</i>	AQ	JP 50-111198	1/28/1974	Japan			X	

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)

<i>LM</i>	AR	Mantz, et al., "Thermolysis of Polyhedral Oligomeric Silsesquioxane (POSS) Macromers and POSS-Siloxane Copolymers", Chem. Mater., 1996, 8, pg. 1250-1259.
<i>LM</i>	AS	Ravi K. Laxman, Neil Hendrix Barry Arkles, Terry A. Tabler "Synthesizing Low-K CVD Materials for Fab Use" Semiconductor International, 11/1/2000

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EXAMINER

V. Manoharan

DATE CONSIDERED

2/24/03

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<i>u</i>	AT	Alfred Grill, et al., "Novel Low-k Dual-Phase Materials Prepared by PECVD, Mat. Res. Soc. Symp. Proc. Vol. 612, 2000 Materials Research Society
<i>u</i>	AU	Albert Wang, et al. "TMCTS for Gate Dielectric in Thin Film Transistors", Mat. Res. Soc. Meeting 1996
<i>u</i>	AV	A. Grill, et al., "Ultralow-k Dielectrics Prepared by Plasma-enhanced Chemical Vapor Deposition", Applied Physics Letters, Vol. 79, No. 6, Aug. 6, 2001.

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